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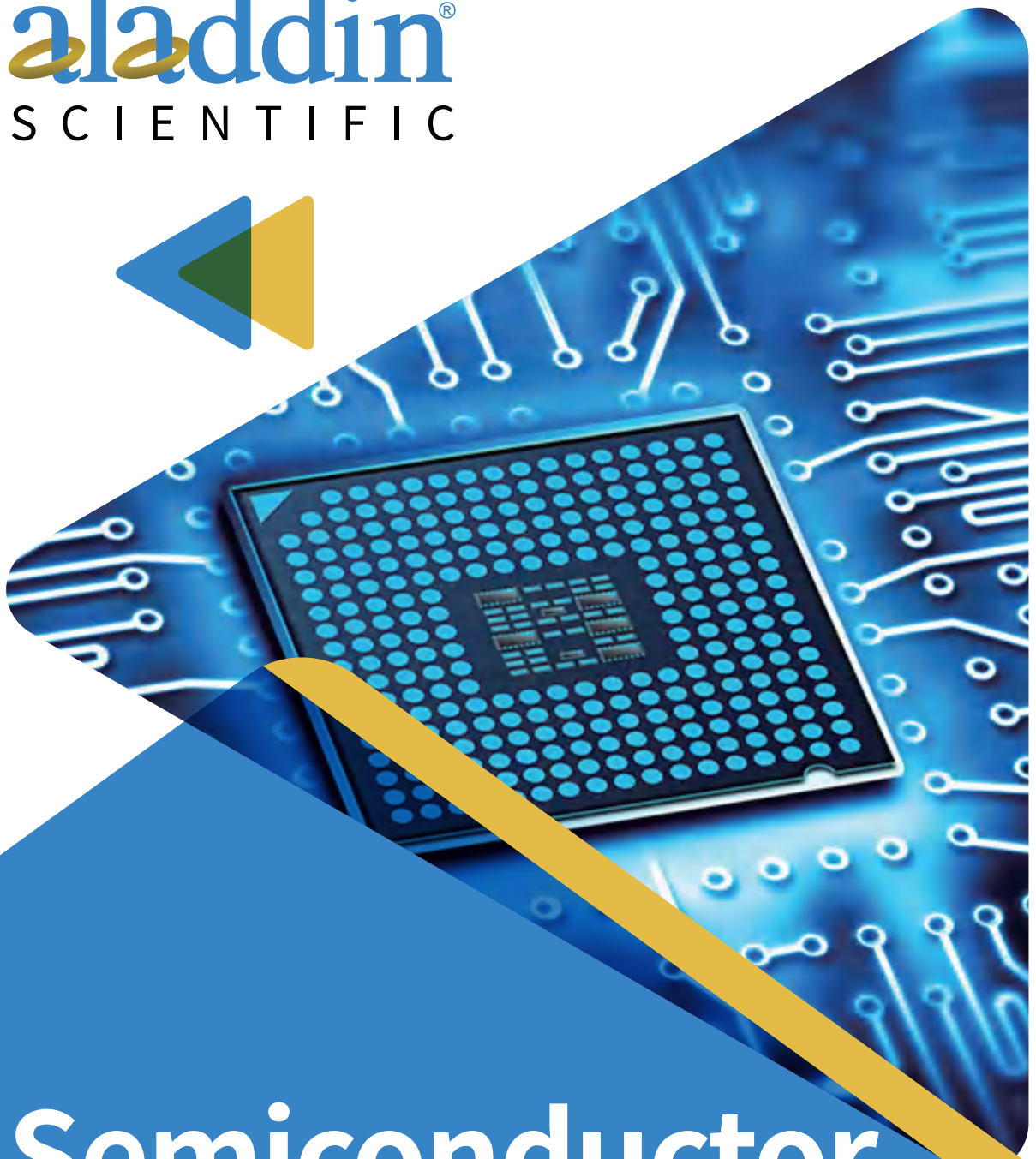

Semiconductor Chemicals

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Introduction

From AI computing chips and optoelectronic devices for 5G base stations to power modules for new energy vehicles, semiconductors have long become the core "cornerstone" supporting emerging technologies. Every step of their R&D and production — from wafer cleaning, thin film deposition, pattern transfer to device packaging — imposes three strict requirements on raw materials: high-purity standards, process-matched product range, and efficient delivery. The quality of raw materials directly determines the reliability of experimental data and the final device yield.

Aladdin Scientific has deep expertise in the research reagent field. With its product system featuring "high-specification, comprehensive product range, and stable supply", it provides end-to-end core reagent support for semiconductors from laboratory R&D to mass production, helping research teams break through technical bottlenecks and accelerate semiconductor innovation.

Product Advantages

High Purity Assurance

Most products adopt PrimorTrace™ grade standards, with metallic impurity levels as low as ppm/ppb, meeting the strict "low-contamination" requirements of advanced semiconductor processes.

Comprehensive Product Range

Product Range: The product portfolio covers wet electronic chemicals, substrates, dielectric materials, CVD/ALD precursors, and photoresist raw materials, spanning the key links of semiconductor manufacturing ("cleaning - film formation - lithography - packaging") and providing a one-stop solution for material needs.

Rapid Spot Delivery

Core products have sufficient spot inventory, shortening R&D and production cycles and preventing process disruptions due to material shortages.

Strict Quality Control

Each batch of products undergoes rigorous quality testing, with complete quality inspection reports provided to ensure batch consistency and reliability.

Application Fields

Integrated Circuit (IC): Silicon substrates, wet electronic chemicals, and photoresist raw materials support CMOS process manufacturing.

Power Devices: Silicon carbide (SiC) and gallium nitride (GaN) enable applications in high-frequency/high-temperature environments.

Optoelectronic Devices: Gallium arsenide (GaAs) and indium phosphide (InP) are used in lasers and modulators.

Advanced Packaging: Dielectric materials and precursor sources ensure the reliability of packaging layers.

Wet Electronic Chemicals — The Key to Precision Cleaning and Etching				
Cat. NO	Product Name	CAS	Grade & Purity	Application
H433855	Hydrogen peroxide solution	7722-84-1	⩾ 99.999% metals basis contains potassium stannate as inhibitor, semiconductor grade, 30-32 wt. % in water	Cleaning and etching of silicon materials
H116237	Hydrofluoric acid	7664-39-3	electronic grade PrimorTrace ™ Ultra ⩾ 99.99998% metals basis 49wt. % in H_2O	Etching of silicon dioxide (SiO_2) and cleaning of quartzware
S399876	Sulfuric acid	7664-93-9	PrimorTrace ™ ⩾ 99.999% metals basis	Used to prepare "piranha" solution (7 parts H_2SO_4 and 3 parts 30% hydrogen peroxide) for cleaning silicon wafers
P123765	Phosphoric acid	7664-38-2	electronic grade	Etching of silicon nitride (Si_3N_4)
H466585	Hydrochloric acid	7647-01-0	PrimorTrace ™ ⩾ 99.999% metals basis 37wt. % in H_2O	Wet cleaning chemical; part of Standard Clean 2 (SC-2) solution for removing heavy metal impurities from silicon
N116245	Nitric acid	7697-37-2	PrimorTrace ™ ⩾ 99.999% metals basis 70%	Etching of phosphosilicate glass (PSG) using mixed solution of HF and HNO_3
A116171	Acetate	64-19-7	electronic grade ⩾ 99.7%	For silicon wafer cleaning, photoresist removal, and etching processes
A431915	Ammonium hydroxide solution	1336-21-6	⩾ 99.99% metals basis 28%-30% NH_3 in H_2O	Cleaning agent
S163080	Sodium hydroxide	1310-73-2	electronic grade ⩾ 99.9% metals basis	Wet etching
T131029	Tetramethylammonium hydroxide solution	75-59-2 (water)	Ultra pure for trace analysis, 25% in H_2O	Developer for positive photoresist
P112287	Potassium hydroxide	1310-58-3	electronic grade ⩾ 99.999% metals basis excludes sodium content	Developer for positive photoresist
W119424	Water	7732-18-5	Deionized	Widely used for rinsing silicon wafers and diluting cleaning agents
I419710	Isopropyl Alcohol (IPA)	67-63-0	PrimorTrace ™ electronic grade ⩾ 99.999% metals basis	General-purpose cleaning agent
A399711	Acetone	67-64-1	UltraPureChrom ™ HPLC grade for HPLC ⩾ 99.9%	General-purpose cleaning agent (more potent than IPA)
T100715	Trichloroethylene	79-01-6	ACS ⩾ 99.5%	Cleaning solvent for silicon wafers and general applications
X112054	Xylene	1330-20-7	ACS ⩾ 98.5% isomers plus ethylbenzene	For removing surface contaminants and photoresist from silicon wafers

Substrate Materials — The Foundation of Semiconductor Devices				
Cat. NO	Product Name	CAS	Grade & Purity	Application
F108390	Ferrocene	102-54-5	⩾ 99%	For doping and electrode deposition
B283697	BIS(CYCLOPENTADIENYL)MAGNESIUM	1284-72-6	⩾ 99.9998% metals basis	For doping and electrode deposition
T109127	Titanium	7440-32-6 (powder)	PrimorTrace ™ ⩾ 99.99% metals basis powder, ⩾ 300mesh	For the preparation of transistors, resistors, capacitors, etc.
H106102	Hafnium	7440-58-6	⩾ 99.9% metals basis 1-10mm	For the preparation of transistors, resistors, capacitors, etc.
A434752	Aluminum	7429-90-5	PrimorTrace ™ ⩾ 99.999% metals basis pellets, 3-8 mesh	For the preparation of transistors, resistors, capacitors, etc.
P104469	Phosphorus red	7723-14-0	PrimorTrace ™ ⩾ 99.999% metals basis lumps, 1-5mm	For the preparation of transistors, resistors, capacitors, etc.
B105888	Boron	7440-42-8	PrimorTrace ™ ⩾ 99.99% metals basis powder, ⩾ 300mesh	For the preparation of transistors, resistors, capacitors, etc.
S105195	Selenium	7782-49-2	PrimorTrace ™ ⩾ 99.999% metals basis D50 ⩾ 80mesh	For the preparation of transistors, resistors, capacitors, etc.
T130110	Tellurium	13494-80-9	PrimorTrace ™ ⩾ 99.999% metals basis ⩾ 100mesh	For the preparation of transistors, resistors, capacitors, etc.
N140012	Nano-diamond powder	7782-40-3	⩾ 99% 30-50nm	For the preparation of transistors, resistors, capacitors, etc.
C105151	Germanium	7440-56-4	PrimorTrace ™ ⩾ 99.999% metals basis 1-3mm	For the preparation of transistors, resistors, capacitors, etc.
G105132	Gallium	7440-55-3	PrimorTrace ™ Ultra ⩾ 99.99999% metals basis	For the preparation of transistors, resistors, capacitors, etc.
T108796	Tin	7440-31-5	PrimorTrace ™ ⩾ 99.999% metals basis granular, 1-6mm	For the preparation of transistors, resistors, capacitors, etc.
S108980	Silicon	7440-21-3	PrimorTrace ™ ⩾ 99.99% metals basis 1-3mm	Mainstream CMOS
S104650	Silicon carbide	409-21-2	⩾ 99.9% metals basis	Wide bandgap; Suitable for harsh environments
G119228	Gallium nitride	25617-97-4	PrimorTrace ™ ⩾ 99.99% metals basis	Typically epitaxially grown on silicon or sapphire
G119227	Gallium arsenide	1303-00-0	PrimorTrace ™ ⩾ 99.999% metals basis pieces	High electron mobility
I119217	Indium(III) phosphide	22398-80-7	⩾ 99.998% metals basis 3-20mesh	For lasers, modulators, and high-frequency applications

Dielectric Materials — The Core Barrier for Insulation and Protection

Cat. NO	Product Name	CAS	Grade & Purity	Application
S305533	Silica micropowder	14808-60-7	⩾ 99.9% metals basis sphere, 35μm	Gate oxide, interlayer dielectric, and isolation
S106133	Silicon nitride	12033-89-5	⩾ 99.9% metals basis α-phase	Passivation and spacer layer

CVD/ALD Precursors — The Core Raw Materials for Thin Film Deposition

Cat. NO	Product Name	CAS	Grade & Purity	Application
N303439	Niobium(V) ethoxide (NbOEt)	3236-82-6	⩾ 99.95% metals basis	For CVD and ALD of thin film materials
H281777	Hexakis(dimethylamino) dialuminum 98%	32093-39-3	⩾ 98%, ⩾ 99.9% metals basis	For CVD and ALD of thin film materials
B283568	Bis(diethylamino)silane	27804-64-4	⩾ 99%	For CVD and ALD of thin film materials
G168548	Germanium(IV) isopropoxide	21154-48-3	⩾ 97%	For CVD and ALD of thin film materials
T282622	(t-Butylimido) tris(diethylamino) niobium(V)	210363-27-2	⩾ 98%	For CVD and ALD of thin film materials
P283060	Pentakis (dimethylamino) tantalum(V)	19824-59-0	PrimorTrace ™ ⩾ 99.99% metals basis	For CVD and ALD of thin film materials
T475149	Tetrakis(diethylamido) hafnium(IV)	19824-55-6	PrimorTrace ™ ⩾ 99.99% metals basis	For CVD and ALD of thin film materials
B300530	Tetrakis(dimethylamido) zirconium	19756-04-8	⩾ 95%	For CVD and ALD of thin film materials
L110963	Lithium tert-butoxide	1907-33-1	⩾ 97%	For CVD and ALD of thin film materials
B281779	Bis(t-butylamino)silane	186598-40-3	⩾ 98%	For CVD and ALD of thin film materials
B115829	Barium bis(2,2,6,6-tetramethyl-3,5-heptanedionate) hydrate	17594-47-7	⩾ 98%	For CVD and ALD of thin film materials
T283555	Tetrakis (ethylmethylamino) zirconium(IV)	175923-04-3	⩾ 99%	For CVD and ALD of thin film materials
T282369	Tetrakis (ethylmethylamino) titanium	175923-03-2	⩾ 99%(99.99%-Ti)	For CVD and ALD of thin film materials
T283058	(t-Butylimido)tris (diethylamino) tantalum(V)	169896-41-7	⩾ 98%	For CVD and ALD of thin film materials
C299989	Cyclopentadienyllithium	16733-97-4	⩾ 95%	For CVD and ALD of thin film materials
T141382	Tin acetylacetonate	16009-86-2	⩾ 99.9% metals basis	For CVD and ALD of thin film materials

CVD/ALD Precursors — The Core Raw Materials for Thin Film Deposition				
Cat. NO	Product Name	CAS	Grade & Purity	Application
Y115831	Yttrium(III) Tris(2,2,6,6-tetramethyl-3,5-heptanedionate)	15632-39-0	⩾ 99%	For CVD and ALD of thin film materials
T283554	Tris(dimethylamino)silane	15112-89-7	⩾ 95%	For CVD and ALD of thin film materials
B282502	Bis(2,2,6,6-tetramethyl-3,5-heptanedionato) nickel(II)	14481-08-4	⩾ 97%	For CVD and ALD of thin film materials
G107856	Gallium acetylacetonate	14405-43-7	PrimorTrace ™ ⩾ 99.99% metals basis	For CVD and ALD of thin film materials
T283248	Tris(2,2,6,6-tetramethyl-3,5-heptanedionato) bismuth(III)	142617-53-6	⩾ 98%	For CVD and ALD of thin film materials
T113664	Tungsten hexacarbonyl	14040-11-0	⩾ 97%	For CVD and ALD of thin film materials
T757491	Tetrakis(diethylamido) zirconium (IV)	13801-49-5	⩾ 99.99% metals basis	For CVD and ALD of thin film materials
T282583	Tris(cyclopentadienyl) yttrium	1294-07-1	⩾ 99.9% metals basis(REO)	For CVD and ALD of thin film materials
B468669	Bis(methylcyclo pentadienyl)nickel(II)	1293-95-4	⩾ 97%	For CVD and ALD of thin film materials
B283543	Bis(cyclopentadienyl) magnesium	1284-72-6	PrimorTrace ™ ⩾ 99.99% metals basis	For CVD and ALD of thin film materials
B138133	Bis(cyclopentadienyl) cobalt	1277-43-6		For CVD and ALD of thin film materials
T283004	Tris(i-propylcyclo pentadienyl)cerium(III)	122528-16-9	⩾ 99.9% metals basis(REO)	For CVD and ALD of thin film materials
C282631	Cycloheptatriene molybdenum tricarbonyl	12125-77-8	⩾ 99%	For CVD and ALD of thin film materials
D166511	Dicarbonylcyclo pentadienyl cobalt(I)	12078-25-0	⩾ 95%	For CVD and ALD of thin film materials
B282346	Bis(2,2,6,6-tetramethyl-3,5-heptanedionato) calcium	118448-18-3	⩾ 97%	For CVD and ALD of thin film materials
B282985	Bis(pentamet hylcyclopentadienyl) barium （Containing tetrahydrofuran ligand）	112379-49-4	PrimorTrace ™ ⩾ 99.99% metals basis	For CVD and ALD of thin film materials
T282967	Tetrakis(dimethylamino) tin(IV)	1066-77-9	⩾ 99.9% metals basis	For CVD and ALD of thin film materials
A299740	Antimony(III) ethoxide	10433-06-4	⩾ 99.9% metals basis	For CVD and ALD of thin film materials
F108390	Ferrocene	102-54-5	⩾ 99%	For CVD and ALD of thin film materials
B282400	Bis(ethylcyclo pentadienyl)manganese	101923-26-6	⩾ 98%	For CVD and ALD of thin film materials
B294778	Bis(ethylcyclopenta dienyl)ruthenium(II)	32992-96-4	PrimorTrace ™ ⩾ 99.999% metals basis	For CVD and ALD of thin film materials

Photoresist Raw Materials —— The Core Medium for Pattern Transfer				
Cat. NO	Product Name	CAS	Grade & Purity	Application
T405560	4-tert-Butoxystyrene (stabilized with TBC)	95418-58-9	⩾ 98%(GC)	KrF Photoresist Monomers
T695114	tert-Butyl (4-vinylphenyl) carbonate	87188-51-0	⩾ 98%	KrF Photoresist Monomers
V162963	2-Vinylphenyl Acetate (stabilized with Phenothiazine)	63600-35-1	⩾ 93%(GC)	KrF Photoresist Monomers
V107256	4-Acetoxystyrene	2628-16-2	⩾ 97%	KrF Photoresist Monomers
A101360	9-Anthroic acid	723-62-6	Moligand ™ ⩾ 98%	KrF Photoresist Monomers
D115834	Dicyclopentadiene diepoxide	81-21-0	⩾ 97%	KrF Photoresist Monomers
A124641	9-Anthracenylmethyl methacrylate	31645-35-9	⩾ 98%	KrF Photoresist Monomers
B152365	9,9-Bis (4-glycidyloxyphenyl) fluorene	47758-37-2	⩾ 98%	KrF Photoresist Monomers
M404740	1-Methylcyclopentyl Methacrylate (stabilized with MEHQ)	178889-45-7	⩾ 98%	ArF Photoresist Monomers
E404442	1-Ethylcyclopentyl Methacrylate (stabilized with MEHQ)	266308-58-1	⩾ 98%(GC)	ArF Photoresist Monomers
A404639	1-Adamantyl Methacrylate (stabilized with MEHQ)	16887-36-8	⩾ 98%	ArF Photoresist Monomers
M158412	2-Methacryloyloxy-2-methyladamantane (stabilized with MEHQ)	177080-67-0	⩾ 97%(GC)	ArF Photoresist Monomers
E156351	2-Ethyl-2-methacryloy-loxyadamantane	209982-56-9	⩾ 97% Contains a stabilizer	ArF Photoresist Monomers
I157611	2-Isopropyl-2-methacry-loyloxyadamantane	297156-50-4	⩾ 98%(GC)	ArF Photoresist Monomers
H157098	3-Hydroxy-1-methacry-loyloxyadamantane	115372-36-6	⩾ 98%(GC)	ArF Photoresist Monomers
T107432	2,2,2-Trifluoroethyl methacrylate	352-87-4	⩾ 98% contains 100 ppm MEHQ as inhibitor	ArF Photoresist Monomers
A151729	4-Acryloylmorpholine	5117-12-4	⩾ 98%(GC) stabilized with MEHQ	UV Photoresist Monomers
I157699	Isobornyl Acrylate (stabilized with MEHQ)	5888-33-5	⩾ 85%(GC)	UV Photoresist Monomers
H103044	2-Hydroxyethyl methacrylate （HEMA）	868-77-9	⩾ 96% contains 250 ppm MEHQ as stabilizer	UV Photoresist Monomers
D154587	2,2-Diethoxyacetophenone	6175-45-7	⩾ 95%(GC)	Photoinitiator-DEAP
E105742	2-Ethylanthraquinone	84-51-5	⩾ 97%	Photoinitiator-EAQ

Photoresist Raw Materials —— The Core Medium for Pattern Transfer				
Cat. NO	Product Name	CAS	Grade & Purity	Application
P133611	4-(P-tolylthio)benzophenone	83846-85-9	⩾ 98%(HPLC)	Photoinitiator-BMS
M303495	(4-Isobutylphenyl) (4-methylphenyl)iodonium Hexafluorophosphate (ca. 70% in Propylene Carbonate)	344562-80-7	⩾ 70%	Photoinitiator-250
B152609	2,2'-Bis(2-chlorophenyl)-4,4',5,5'-tetraphenyl-1,2'-biimidazole [Photopolymerization Initiator]	7189-82-4	⩾ 97%(T)	Photoinitiator-BCIM
T304464	Diphenyl(4-phenylthio) phenylsufonium Hexafluoroantimonate	71449-78-0	⩾ 98%	PhotoinitiatorUVI-6976
B110135	4,4' -Bis(diethylamino) benzophenone	90-93-7	⩾ 99%	Photoinitiator-EMK
M130040	2-Methyl-1-[4-(methylthio) phenyl] -2-morpholino-1-propanone	71868-10-5	⩾ 98%	Photoinitiator-907
T107643	Diphenyl(2,4,6-trimethylbenzoyl)phosphine oxide	75980-60-8	⩾ 97%	Photoinitiator-TPO
I138984	2-Isopropylthioxanthone	5495-84-1	⩾ 98%(GC)	Photoinitiator-ITX
B105178	2,2-Dimethoxy-2-phenylacetophenone	24650-42-8	⩾ 99%	Photoinitiator-BDK
H110280	2-Hydroxy-2-methylpropiophenone	7473-98-5	⩾ 97%	Photoinitiator-1173
H110064	1-Hydroxycyclohexyl Phenyl Ketone	947-19-3	⩾ 98%	Photoinitiator-184
D154567	2,4-Diethylthioxanthen-9-one	82799-44-8	⩾ 98%	Photoinitiator-DETX
D135366	2-Dimethylaminoethyl Benzoate	2208-05-1	⩾ 97%(GC)	Photoinitiators (Photosensitizers)
B131530	Bis(4-tertButylphenyl) iodonium hexafluorophosphate	61358-25-6	⩾ 98%(HPLC)	Photoinitiators (Photosensitizers)
P105723	Propylene carbonate	108-32-7	⩾ 99%	Other Types of Photoresist Raw Materials
B131786	Bisphenol A Diglycidyl Ether （BADGE）	1675-54-3	Moligand ™ ⩾ 85%	Other Types of Photoresist Raw Materials
P136148	[(Phenylmethoxy)methyl] oxirane (Benzyl Glycidyl Ether)	2930-05-4	⩾ 97%(GC)	Other Types of Photoresist Raw Materials
E404418	1-Ethylcyclohexyl Methacrylate (stabilized with MEHQ)	274248-09-8	⩾ 98%	Other Types of Photoresist Raw Materials
E404440	1-Ethylcyclopentyl Acrylate (stabilized with MEHQ)	326925-69-3	⩾ 97%	Other Types of Photoresist Raw Materials

Photoresist Raw Materials —— The Core Medium for Pattern Transfer				
Cat. NO	Product Name	CAS	Grade & Purity	Application
M404745	1-Methylcyclopentyl Acrylate (stabilized with MEHQ)	178889-49-1	⩾ 98%(GC)	Other Types of Photoresist Raw Materials
M158411	Mevalonic Lactone Methacrylate (stabilized with MEHQ)	177080-66-9	⩾ 98%(GC)	Other Types of Photoresist Raw Materials
B104512	tert-Butyl methacrylate (TBMA)	585-07-9	contains 200 ppm monomethyl ether hydroquinone as inhibitor 99%	Other Types of Photoresist Raw Materials
B102363	1,4-Butanediol dimethacrylate	2082-81-7	⩾ 95% contains 100 ppm monomethyl ether hydroquinone as inhibitor	Other Types of Photoresist Raw Materials
E106223	Ethylene glycol dimethacrylate	97-90-5	⩾ 98% contains 90 - 110 ppm MEHQ as stabilizerr	Other Types of Photoresist Raw Materials
H167113	2,2,3,3,4,4,4-Heptafluoro-butyl methacrylate (stabilized with MEHQ)	13695-31-3	⩾ 97%	Other Types of Photoresist Raw Materials
E102093	2-Ethylhexyl methacrylate （EHMA）	688-84-6	⩾ 99%, contains 90-110 ppm MEHQ as stabilizer	Other Types of Photoresist Raw Materials
I132125	N-Isopropylmethacry-lamide	13749-61-6	⩾ 97%	Other Types of Photoresist Raw Materials
D102672	2-(Diethylamino)ethyl methacrylate	105-16-8	⩾ 99%	Other Types of Photoresist Raw Materials
M138825	Methyl 2-(bromomethyl) acrylate	4224-69-5	⩾ 97%	Other Types of Photoresist Raw Materials
H109880	Hydroxypropyl methacrylate (HPMA)	27813-02-1	⩾ 97% stabilized with s0.02% 4-methoxyphenol	Other Types of Photoresist Raw Materials
A302509	3-Acryloxypropyl Methyl Dimethoxysilane	13732-00-8	⩾ 98% Contains stabilizer	Other Types of Photoresist Raw Materials
O404835	2-Oxohexahydro-2H-3,5-methanocyclopenta[b]furan-6-yl Methacrylate	254900-07-7	⩾ 98%(GC)	Other Types of Photoresist Raw Materials
I102358	Isobornyl methacrylate	7534-94-3	50-150 ppm MEHQ stabilizer	Other Types of Photoresist Raw Materials
A151188	1-Acryloyloxy-3-hydroxyadamantane	216581-76-9	⩾ 98%(GC)	Other Types of Photoresist Raw Materials
A302637	Adamantan-1-yl Acrylate (stabilized with BHT)	121601-93-2	⩾ 99%	Other Types of Photoresist Raw Materials
M404717	2-Methyladamantan-2-yl Acrylate (stabilized with MEHQ)	249562-06-9	⩾ 98%	Other Types of Photoresist Raw Materials
E730509	2-Ethyl-2-adamantyl acrylate	303186-14-3	⩾ 99%	Other Types of Photoresist Raw Materials
D124377	Dicyclopentanyl Methacrylate	34759-34-7	⩾ 95%(GC) contains MEHQ as stabilizer	Other Types of Photoresist Raw Materials

Photoresist Raw Materials —— The Core Medium for Pattern Transfer				
Cat. NO	Product Name	CAS	Grade & Purity	Application
D180482	2-(2,2-Difluorovinyl) bicyclo[2.2.1]heptane	123455-94-7	⩾ 95%	Other Types of Photoresist Raw Materials
E404456	1-(1-Ethoxyethoxy)-4-vinylbenzene (stabilized with TBC)	157057-20-0	⩾ 96%	Other Types of Photoresist Raw Materials
H588692	4-Hydroxyphenyl methacrylate（stabilized with MQ)	31480-93-0	⩾ 97%	Other Types of Photoresist Raw Materials
B725447	4-(4-(Acryloyloxy)butoxy) benzoic acid	69260-42-0	⩾ 98%	Other Types of Photoresist Raw Materials
P193379	4-Isopropenylphenol	4286-23-1	⩾ 97%	Other Types of Photoresist Raw Materials
V102929	2-Vinylnaphthalene	827-54-3	⩾ 97% stabilized with 0.4% 4-tert-Butylcatechol	Other Types of Photoresist Raw Materials
N343104	N-Hydroxynaphthalimide triflate	85342-62-7	⩾ 98%	Other Types of Photoresist Raw Materials
M158122	5-Methyl-1Hbenzotriazole	136-85-6	⩾ 99%	Other Types of Photoresist Raw Materials
P165933	(4-Phenylthiophenyl) diphenylsulfonium triflate	111281-12-0		Other Types of Photoresist Raw Materials
B476350	Bis(4-tert-butylphenyl) iodonium perfluoro-1-butanesulfonate	194999-85-4	electronic grade ⩾ 99%	Other Types of Photoresist Raw Materials
B152266	Bis(4-tert-butylphenyl) iodonium Trifluoro-methanesulfonate	84563-54-2	⩾ 98%	Other Types of Photoresist Raw Materials
D132479	Diphenyliodonium chloride	1483-72-3	⩾ 98%	Other Types of Photoresist Raw Materials
D154818	Diphenyliodonium Bromide	1483-73-4	⩾ 98%	Other Types of Photoresist Raw Materials
D154819	Diphenyliodonium Iodide	2217-79-0	⩾ 90%	Other Types of Photoresist Raw Materials
T162151	Triphenylsulfonium Bromide	3353-89-7	⩾ 98%(T)	Other Types of Photoresist Raw Materials
T162517	Triphenylsulfonium Tetrafluoroborate	437-13-8	⩾ 98%(HPLC)	Other Types of Photoresist Raw Materials
T167308	Triphenylsulfonium perfluoro-1-butanesufonate	144317-44-2	⩾ 99%	Other Types of Photoresist Raw Materials
T299283	Triphenylsulfonium triflate	66003-78-9	⩾ 99%	Other Types of Photoresist Raw Materials
F167522	(4-Fluorophenyl) diphenylsulfonium triflate	154093-57-9	⩾ 98%	Other Types of Photoresist Raw Materials
T341870	Triphenylsulfonium chloride	4270-70-6	⩾ 98%	Other Types of Photoresist Raw Materials
T114510	Tris-(8-hydroxyquinoline) aluminum	2085-33-8	⩾ 98%	Other Types of Photoresist Raw Materials


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